Development of SiC Large Tapered Crystal Growth

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Project Duration: FY09 to FY11

DOE Vehicle Technologies Program Advanced Power Electronics and Electric Machines Research FY11 Kickoff Meeting

Oak Ridge National Laboratory Oak Ridge, Tennessee

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The Problem

- Majority of very large potential benefits of wide band gap semiconductor power electronics have NOT been realized due in large part to high cost and high defect density of commercial wafers.
- Despite 20 years of development, present SiC wafer growth approach is yet to deliver majority of SiC's inherent performance and cost benefits to power systems.
- Commercial SiC power devices are significantly de-rated in order to function reliably due to the adverse effects of SiC crystal dislocation defects (thousands per cm²) in the SiC wafer

Project Overview

Research Focus Area: Power Electronics

→ Temperature Tolerant Devices

Objective

• Demonstrate initial feasibility of totally new "Large Tapered Crystal" (LTC) process for growing vastly improved large-diameter wide-band gap wafers.

Addresses Targets

- The goal of this research is to experimentally investigate and demonstrate feasibility of the key unproven LTC growth processes in SiC.
 - Laser-assisted growth of long SiC fiber seeds.
 - Radial epitaxial growth enlargement of seeds into large SiC boules.

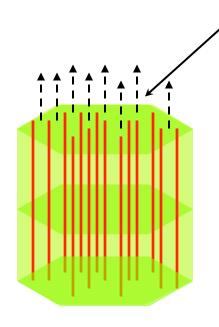
Uniqueness and Impacts

- Open a new technology path to large-diameter SiC and GaN wafers with 1000-fold defect density improvement at 2-4 fold lower cost.
- Leapfrog improvement in wide band gap power device capability and cost.

Description of Technology (4H-SiC)

Existing SiC Wafer Growth Approach

(Sublimation growth or High Temperature CVD)



C-axis (vertical) growth proceeds from top surface of large-area seed crystal via thousands of screw dislocations.

Vertical growth rate would not be commercially viable (i.e., would not be high enough) without high density (> 100 cm⁻²) of screw dislocations.

Crystal enlargement is vertical (up c-axis). Negligible lateral enlargement.

Thermal gradient driven growth at T > 2200 °C High thermal stress/strain

Fundamental Flaw: Abundant screw dislocation defects are needed for present SiC wafer growth approach, yet these same defects harm SiC power device yield and performance (cause blocking voltage de-rating, leakage, etc.)

- High thermal stress also generates dislocations.

Description of Technology (4H-SiC)

Future: Game Changer - Large Tapered Crystal (LTC) Growth

(US Patent 7,449,065 Owned by OAI, Sest, Inc., with NASA Rights)

Vertical Growth Process:
Fiber-like growth of smalldiameter columnar tip region
(from single screw dislocation)

Small-diameter c-axis fiber from single screw dislocation at mm/hour rate.

Lateral Growth Process:

CVD growth enlargement on sidewalls to produce large-diameter boule

(T = 1500 - 2000 °C)

MOST of crystal grown via epitaxy process on laterally expanding taper at significantly lower growth temperature (lower thermal stress) and growth rate.

Completed boule section Ready for slicing into wafers

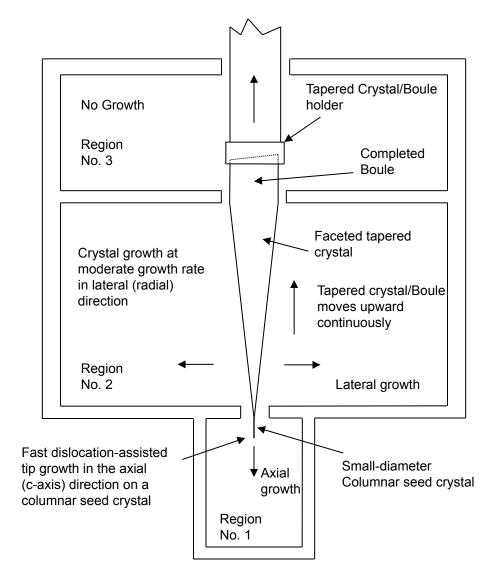
Large diameter wafers yielded at mm/hour (wafers/hour) growth rate!

Tapered portion is then re-loaded into growth system as seed for subsequent boule growth cycle.

Description of Technology

Large Tapered Crystal (LTC) Growth Method

Simplified Schematic Cross-Sectional Representation



Features (one embodiment):

- 1. 3-Region growth apparatus for 3 different growth actions.
- 2. Region 1: Axial (c-axis) growth on a <u>very small diameter</u> columnar portion enables fast growth in the c-axis direction.
- 3. Region 2: Lateral (m-direction) growth at moderate growth rate on the tapered portion
- 4. Region 3: No growth after LTC boule reaches desired diameter.
- 5. Growth rate of boule in caxis direction equals fast growth rate of columnar seed crystal.
- 6. Boule contains only one SD along its axis; the remainder of the boule is nominally defect-free

Description of Technology (Fiber Growth)



Seed Holder Rod

Works for other materials, but this will be first attempt for single-crystal SiC.

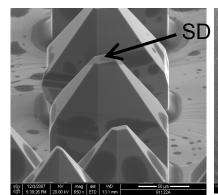
Seed Crystal

~0.5 mm diameter SiC crystal fiber

CO₂ Laser

CO₂ Laser

4H-SiC Seed Crystal





Feed Rod with Si + C + Solvent (Non Single-Crystal Source Material)

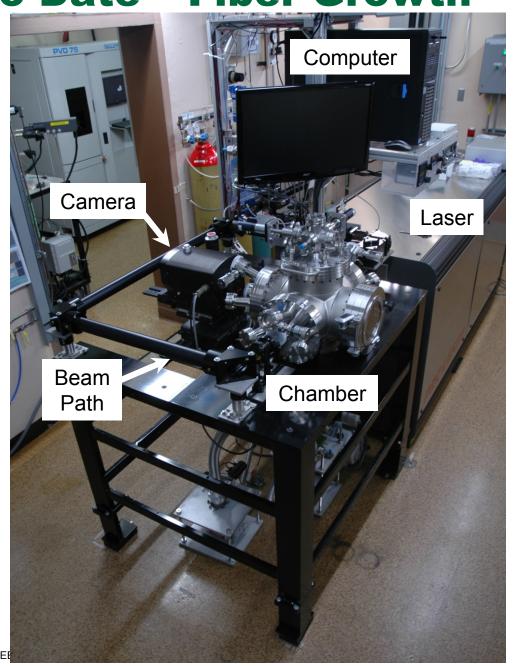


Accomplishments to Date - Overview

- Funding initiated 2 December 2009 (late start).
- Major modifications to NASA Glenn SiC Growth Reactor #2 have been implemented (95% complete).
 - Needed for experimental demonstrations of LTC radial growth enlargement of SiC fibers into boules.
 - Fundamental change in configuration from <u>cold-wall</u> with pancake coil RF heating to hot-wall with barrel coil RF heating.
 - First growth experiment carried out on SiC saw-cut pseudo-fiber October 2010.
- Design and build-up of laser-heated SiC fiber growth system has been implemented (95% complete)
 - Needed for experimental demonstration of LTC fiber growth process.
 - First growth experiment to be conducted November 2010.

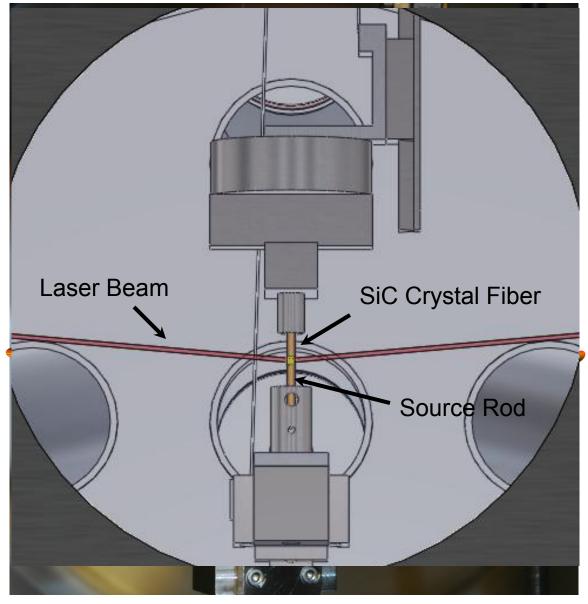
Accomplishments to Date – Fiber Growth

- •Fiber Growth System
 - Design complete
 - •Purchase/fabricate complete
 - •~\$125K new equipment
 - •~\$140K repurposed NASA equipment
 - •Build/assemble complete
 - Control/acquisition software
 - in progress
- Source Material
 - •Identify Si-C solvents complete
 - Feed rod creation process
 - in progress
- •Seed Crystals in progress



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Accomplishments to Date – Fiber Growth





DOE APEEM FY11 Kickoff Meeting

Accomplishments - Radial Growth

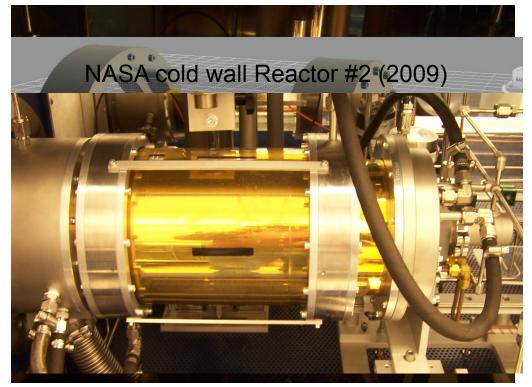
Major modifications to NASA Glenn SiC Growth Reactor #2 to support LTC radial growth demonstrations have been implemented.

Fundamental change in NASA SiC growth configuration from <u>cold-wall</u> with pancake coil RF heating to <u>hot-wall</u> with barrel coil RF heating.

Hot wall system necessary for LTC implementation goals of:

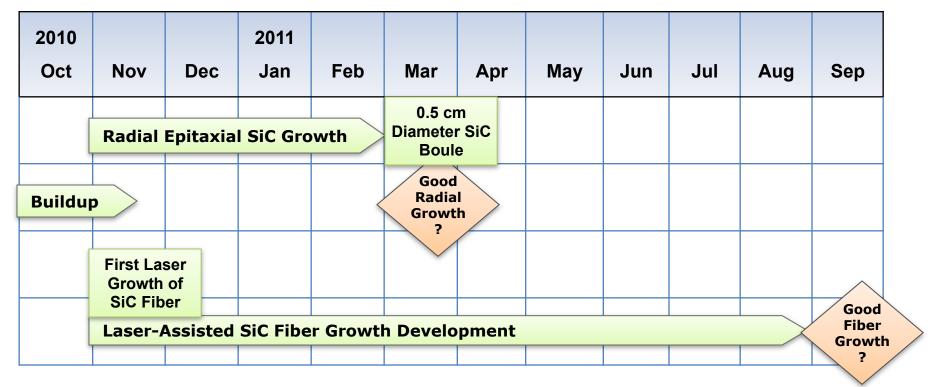
- High growth rate
- Temperature uniformity
- Radial deposition symmetry

Since LHFZ SiC fibers not yet grown, initial radial growth experiments are commencing with thin pieces (flat toothpick-like shape) cut from commercially purchased a-plane and m-plane SiC wafers.





FY11 Approach and Challenges



Go No/Go Decision Point: High quality SiC crystals (of proof-of-principle size) must be

demonstrated for **both** <u>radial</u> and <u>fibe</u>r growth processes.

Challenges/Barriers: Both growth processes are "first ever" experimental

demonstration attempts as methods of SiC growth.

Schedule does not enable major redesign/rebuild of hardware.



Beyond FY11 (Not in present agreement)

• FY12-13

- Launch joint development of full prototype LTC SiC growth system (fiber growth + lateral growth) in collaboration with commercial and/or university development partners.
- Projected Go/No Go: High growth rate of nearly defect-free SiC boules & commercial investment.

FY13-14

- Explore GaN LTC experiments.
- Projected Go/No Go: If a high-quality fiber GaN seed crystal cannot be grown in reproducible manner, then GaN LTC growth is not viable.



Questions



